Call for Papers
for a special issue of *Microelectronic Engineering*

Micro/Nano Fabrication 2015
Short title: Nano Fab 2015

including selected papers from the
41th Micro and Nano Engineering conference MNE 2015

The aim of this special issue is to bring together recent advances in Micro and Nano Fabrication using different techniques. This issue is 'open call'. This means that, while mainly including selected papers presented at MNE2015, it is also open to other authors.

The MNE conference series focuses on micro- & nanofabrication and manufacturing using lithography and other nanopatterning related approaches, as well as the application of micro- and nanostructures and devices in electronics, photonics, electromechanics, environment and life sciences.

The areas of particular interest for this special issue are:

Micro and Nano Fabrication Methods
- **Nano-imprint and soft-lithography:** Stamp fabrication, processes and imprinting methods and modelling, applications, dedicated resists, systems, and alignment.
- **Alternative patterning methods:** Electron- and ion-beam induced deposition and etching, 3D lithography, integration of nano-objects, printing/deposition of nano-particles, -tubes and -rods.
- **Pattern transfer and plasma etching:** Lift-off with new materials, sputtering, milling, atomic layer etching, nanoscale etching, etching of new materials, deep etching, directional (lateral) etching.
- **Micro and nano manufacturing:** Scale-up and transfer to manufacturing, 3D printing, additive techniques, thin film and atomic layer deposition, moulding, rapid prototyping, multi-scale manufacturing, nanometrology, inspection, process diagnostics and control.

Manuscript submission deadline: 23 October, 2015

Manuscripts of the special issues will be submitted and reviewed via the online Elsevier Editorial System (EES). After acceptance, articles will be processed and published with the standard Elsevier publishing timeline for each individual manuscript. Please submit papers directly using the MEE journal submission web page and *select the appropriate special issue*. The submission opens on 22 September, 2015.

Guest Editors
Ageeth Bol (Eindhoven University of Technology, The Netherlands)
Harm Knoops (Oxford Instruments Plasma Technology, United Kingdom and Eindhoven University of Technology, The Netherlands)

Instructions for authors
- The standard submitted manuscripts are regular MEE publications (4-6 pages).
- Review papers (7-10 pages) are encouraged from invited/plenary speakers and leading members of the community. If you are not an MNE invited speaker and you wish to submit a review, please contact Evangelos Gogolides (Editor-in-Chief, Microelectronic Engineering) or one of the Guest Editors with a proposal and outline.
- Highly novel work can be submitted as an *accelerated* publication (up to 4 pages) and will be given high priority.
- For all publications, we encourage you to include supplementary data and audio/video abstracts.
- For general enquiries, please contact Luigi Sasso, MNE Program Co-Chair.
- Please select the correct file type (regular paper, review paper, etc.) and choose the correct name of the special issue **Nano Fab 2015**.

Your paper and associated supplementary information should comprise a complete, novel and full description of your work. Please make sure that your paper is well-written, and supply additional information, videos, audios, etc. as on-line supplementary material to appear on the web, but not in the printed version (see instructions for authors). Your supplementary material will be available directly from ScienceDirect or Scopus.

Please note that the special issue papers undergo the same high-standard review process as any other MEE paper. At least two reviews need to be in agreement per paper before decision, and the typical rejection rate is 50-60%. Therefore, please make sure that both the technical content of your paper, and your presentation style and language, is of high quality, novel, unpublished, and not being submitted elsewhere. Please check the author guidelines.